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- (74) Agents: OKABE, Masao et al.; No. 602, Fuji Bldg., 2-3, Marunouchi 3-chome, Chiyoda-ku, Tokyo 1000005 (JP).
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- (71) Applicant (for all designated States except US): CANON KABUSHIKI KAISHA [JP/JP]; 3-30-2, Shimomaruko, Ohta-ku, Tokyo 1468501 (JP).
- (72) Inventors; and
- (75) Inventors/Applicants (for US only): SHIBA, Shoji [JP/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 1468501 (JP). ISHIKURA, Hiroe [JP/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 1468501 (JP). OKANO, Akihiko [JP/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 1468501 (JP).
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(54) Title: PHOTSENSITIVE RESIN COMPOSITION, METHOD OF FORMING LEVEL DIFFERENCE PATTERN USING THE PHOTSENSITIVE RESIN COMPOSITION, AND METHOD OF PRODUCING INK JET HEAD

(57) Abstract: To provide a positive type photosensitive resin composition, containing at least an acrylic resin having a carboxylic anhydride structure in a molecule, and a compound that generates an acid when irradiated with light.

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